



**FOR IMMEDIATE RELEASE**

**D2S CEO AKI FUJIMURA NAMED A SPIE FELLOW**

*Aki Fujimura recognized by SPIE for his technical leadership in applying GPU acceleration to semiconductor manufacturing software, significant service to SPIE, and industry collaboration through the eBeam Initiative*

**SAN JOSE, Calif., September 26, 2023**—D2S, a supplier of GPU-accelerated solutions for semiconductor manufacturing, today announced that Aki Fujimura, chairman and CEO of D2S, has been recognized as a Fellow by SPIE, the international society for optics and photonics. Each year, the SPIE Fellows program recognizes members of the society who have made significant scientific and technical contributions in the fields of optics, photonics and imaging. Mr. Fujimura will formally accept the honor at the SPIE Photomask Technology + EUV Lithography Conference to be held in Monterey, Calif., next week.

Mr. Fujimura is widely known as a pioneer and evangelist in developing and promoting the use of GPU accelerated hardware and software to optimize photomask and semiconductor design and manufacturing. His work in GPU-accelerated computing has greatly facilitated the industry's shift to the pixel-domain for leading-edge mask making, including enabling the use of curvilinear mask features to improve wafer quality, as well as for implementing deep learning for electronics manufacturing.

Prior to D2S, Mr. Fujimura was chief technology officer at Cadence Design Systems. He returned to Cadence for the second time through the acquisition of Simplex Solutions where he was president, chief operating officer and inside board member. He was also an inside board member and vice president at Pure Software. He was a founding member of Tangent Systems in 1984 (whose place and route contributions that he co-invented are still in use today), which was subsequently acquired by Cadence Design Systems in 1989.

Mr. Fujimura has provided significant service to SPIE. He has served on the conference program committee for the SPIE Photomask Technology Conference every year since 2012, has been a supporter of SPIE initiatives such as the BACUS newsletter and webinar series, and a strong contributor to the Journal of Micro/Nanopatterning, Materials, and Metrology (JM<sup>3</sup>). In addition, he has authored or co-authored papers presented at nearly every SPIE Photomask Technology conference since 2010, as well as papers presented at the SPIE Advanced Lithography + Patterning and SPIE Photomask Japan conferences. Several of these received best paper awards, including at SPIE Photomask Japan in 2010 (1) and at SPIE Photomask + EUV Lithography in 2019 and 2022 (2, 3).



“I think that Aki Fujimura merited election to SPIE Fellow based on both his technical accomplishments and his visionary leadership in electronic design automation. He was an early proponent of using non-Manhattan geometries, such as X Architecture place-and-route, for improving device performance, and more recently Aki has been an inspiring advocate for the use of curvilinear features, on both masks and wafers. At conferences such as Photomask Technology we now see increasing interest in and use of curvilinear patterns,” stated Dr. Harry Levinson, principal lithographer, HJL Lithography.

Mr. Fujimura is also a co-founder of the eBeam Initiative, a consortium of more than 50 companies from across the semiconductor ecosystem that serves as an educational forum for the advancement of new semiconductor design-to-manufacturing approaches based on electron-beam (eBeam) technologies. To support its mission of education and promotion for the photomask and semiconductor industry, the eBeam Initiative established multiple annual meetings, which take place during the SPIE Advanced Lithography + Patterning conference and the SPIE Photomask Technology conference. For the past 12 years during SPIE Photomask Technology, the eBeam Initiative has presented results of its annual Luminaries Survey, which captures the opinions of business and technology experts throughout the semiconductor ecosystem to provide early insight into key market and technology trends.

In addition, Mr. Fujimura co-founded the Center for Deep Learning in Electronics Manufacturing (CDLe), an alliance of industry leaders to advance the state-of-the-art in deep learning – a subset of artificial intelligence (AI) and machine learning – in order to improve the respective offerings of its members. He is also a member of the governing council for the Electronic System Design (ESD) Alliance. To date, he holds more than 100 patents and has more than 40 publications. He received his B.S. and M.S. in electrical engineering from MIT.

For more information about the SPIE Fellows program, visit <https://spie.org/membership/member-recognition/spie-fellows/>.

#### **References for Best Paper Awards**

- (1) “Best depth of focus on 22nm logic wafers with less shot count,” SPIE Photomask Japan 2010
- (2) “Study of Mask and Wafer Co-design That Utilizes a New Extreme SIMD Approach to Computing in Memory Manufacturing — Full-Chip Curvilinear ILT in a Day,” co-authored with Micron, SPIE Photomask + EUV Lithography 2019 (second place)
- (3) “You don’t need 1nm contours for curvilinear shapes: pixel-based computing is the answer,” SPIE Photomask + EUV Lithography 2022 (first place)



**About D2S**

D2S is a supplier of GPU-accelerated solutions for semiconductor manufacturing. The company provides simulation-based custom solutions to leading equipment partners and D2S TrueMask® solutions to photomask and wafer manufacturers. D2S TrueMask solutions use the D2S Computational Design Platform to enable advanced photomask designs using complex rectilinear and curvilinear shapes for superior wafer quality within practical, cost-effective write-times. D2S is the managing sponsor of the eBeam Initiative and a founding member of the Center for Deep Learning in Electronics Manufacturing (CDLe). Headquartered in San Jose, Calif., the company was founded in 2007. For more information, see: [www.design2silicon.com](http://www.design2silicon.com).

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